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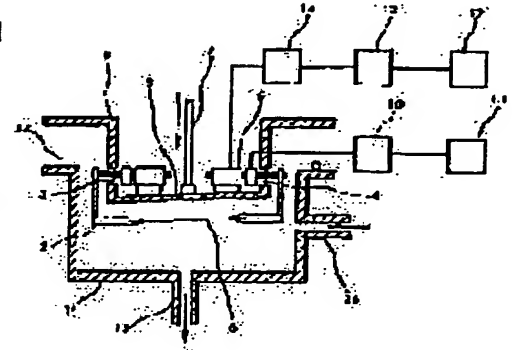
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(54) DUSTFREE CLAMPING METHOD FOR WAFER

(57)Abstract:

PURPOSE: To enable cleaning in a dustfree, low-stress, ultra clean environment by rectilinearly moving a plurality of clamping pawls to diagonally clamp a wafer, and separating a mechanical section from the clamping pawls on drive axis by means of a diaphragm.

CONSTITUTION: A cleaning equipment consists of a cleaning bath 1 and its lid 9 including the chamber 8 of a mechanism for driving pawls to clamp a wafer. The pawl driving mechanism chamber 8 consists of driving motors 5 and pressure sensors 4. The mechanism horizontally drives clamping pawls 2, separated therefrom by a diaphragm 3, on the cleaning bath 1 side to clamp a wafer. A plurality of the clamping pawls 2 are different from each other in length in the direction of opposite side. When receiving a wafer 6, therefore, the pawls 2 clamps it with a certain inclination. This obtains wafers free from spontaneous oxide films which are necessary in the development of devices with 0.3 μ m or below.



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